

ABSTRACT

There is provided an illumination system for lithography with wavelengths of ≤ 193 nm. The system comprises a first optical element, which is divided into first raster elements and lies in a first plane. The first plane defines an x-direction and a y-direction, the first raster elements each have an x-direction and a y-direction with an aspect ratio, and at least two of the first raster elements have aspect ratios of different magnitude.

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